This listing of claims will replace all prior versions, and listings of claims in the application:

Listing of Claims:

C1 1. (Currently Amended) An exposure method of forming patterns of a plurality of layers on a substrate using a plurality of exposure apparatus, comprising:

adjusting an image forming characteristic of a first exposure apparatus in said plurality of exposure apparatus to expose one layer ~~of said substrate~~ in consideration of ~~a stored~~ an image distortion correction capability of a second exposure apparatus which is different from said first exposure apparatus, one of the first and second exposure apparatus being a scanning type exposure apparatus and the other being a stationary type exposure apparatus; and

~~transferring said substrate from the first exposure apparatus to the second exposure apparatus; and~~

exposing another layer ~~of said substrate~~ by using said second exposure apparatus.

2. (Cancelled)

3. (Currently Amended) The exposure method according to ~~Claim 2~~ Claim 1, further comprising:

adjusting an image forming characteristic of the second exposure apparatus in consideration of ~~a stored~~ an image distortion correction capability of said first exposure apparatus.

4. (Original) The exposure method according to Claim 1, wherein said first apparatus and said second apparatus are used in said exposure of layers in sequence.

5. (Currently Amended) The exposure method according to Claim 4, wherein the second exposure apparatus exposes another layer of the substrate after the first exposure apparatus exposes said one layer of the substrate ~~said first apparatus includes one of a stationary type exposure apparatus in which a mask and said substrate are almost stationary during exposure and a scanning type exposure apparatus in which a mask and said substrate are synchronously moved during exposure, and said second apparatus includes the other of the stationary type exposure apparatus and the scanning type exposure apparatus~~.

cont C1

6-7. (Cancelled)

8. (Currently Amended) The exposure method according to ~~Claim 7~~ Claim 1, wherein

said second exposure apparatus is a scanning type exposure apparatus which moves said mask and said substrate synchronously during exposure, and

said image forming characteristic of said first exposure apparatus is adjusted so as to reduce an axially symmetrical image distortion component ~~that can not be sufficiently corrected by said scanning type exposure apparatus~~.

9. (Currently Amended) The exposure method according to ~~Claim 7~~ Claim 1, wherein

said second exposure apparatus is a stationary type exposure apparatus in which said mask and said substrate are almost stationary during exposure, and

said image forming characteristic of said first exposure apparatus is adjusted so as to reduce an image distortion including a rectangular component ~~and parallelogrammatic component that can not be sufficiently corrected by said stationary type exposure apparatus~~.

10. (Currently Amended) An exposure method of transferring a pattern of a first mask onto a substrate using a first exposure apparatus, ~~and of further transferring a pattern of a second mask onto said substrate using a second exposure apparatus, said method~~ comprising:

cont c1

adjusting an image forming characteristic of said first exposure apparatus, in accordance with ~~stored~~ information on an image distortion correction capability of ~~said~~ a second exposure apparatus which is different from said first exposure apparatus, one of the first and second exposure apparatus being a scanning type exposure apparatus and the other being a stationary type exposure apparatus; and

~~transferring said pattern of said first mask onto said substrate~~

exposing said pattern of said first mask onto said substrate .

11-12. (Cancelled)

13. (Currently Amended) The exposure method according to ~~Claim 12~~ Claim 10, wherein

said second exposure apparatus is a scanning type exposure apparatus which moves said mask and said substrate synchronously during exposure, and

said image forming characteristic of said first exposure apparatus is adjusted so as to leave at least one of image distortion components of a rectangular component and a parallelogrammatic component ~~that can be corrected by said scanning type exposure apparatus remains on said substrate~~ .

cont c1

14. (Currently Amended) The exposure method according to ~~Claim 12~~ Claim 10, wherein

said second exposure apparatus is a stationary type exposure apparatus in which said mask and said substrate are almost stationary during exposure, and

said image forming characteristic of said first exposure apparatus is adjusted so as to leave at least one of image distortion components of a trapezoidal component and an axially symmetrical component ~~that can be corrected by said stationary type exposure apparatus remains on said substrate~~.

15-25. (Cancelled)

26-42. (Withdrawn)

43. (Original) A device manufacturing method including a lithographic process, wherein

exposure is performed using the method according to Claim 1 in said lithographic process.

44-45. (Cancelled)

46. (Original) A device manufacturing method including a lithographic process, wherein

cont C1

exposure is performed using the method according to Claim 10 in said lithographic process.

47-48. (Cancelled)

49-51. (Withdrawn)

52. (New) The exposure method according to Claim 1, wherein said first exposure apparatus roughly corrects one image distortion component and finely corrects another image distortion component, based on the image distortion correction capability of the second exposure apparatus.

53. (New) The exposure method according to Claim 52, wherein said first exposure apparatus roughly corrects the one image distortion component which can be finely corrected by the second exposure apparatus.

54. (New) The exposure method according to Claim 1, wherein said second exposure apparatus is the scanning type exposure apparatus, and the image forming characteristic of the first exposure apparatus is adjusted so as to reduce a trapezoidal image distortion component.

cont C1

55. (New) The exposure method according to Claim 1, wherein said second exposure apparatus is the scanning type exposure apparatus, and the image forming characteristic of the first exposure apparatus is adjusted so as to leave a rectangular image distortion component.

56. (New) The exposure method according to Claim 1, wherein said second exposure apparatus is the scanning type exposure apparatus, and the image forming characteristic of the first exposure apparatus is adjusted so as to leave a prallelogrammatic image distortion component.

57. (New) The exposure method according to Claim 1, wherein said second exposure apparatus is the stationary type exposure apparatus, and the image forming characteristic of the first exposure apparatus is adjusted so as to leave a trapezoidal image distortion component.

58. (New) The exposure method according to Claim 1, wherein said second exposure apparatus is the stationary type exposure apparatus, and the image forming characteristic of the first exposure apparatus is adjusted so as to leave an axially symmetrical image distortion component.

cont C1

59. (New) The exposure method according to Claim 1, wherein the image forming characteristic of the first exposure apparatus is adjusted so as to leave an image distortion component which can be finely corrected by the second exposure apparatus.